

Title (en)

INSULATION LAYER MATERIAL FOR MICROELECTRONICS

Title (de)

ISOLATIONSSCHICHTMATERIAL FÜR DIE MIKROELEKTRONIK

Title (fr)

MATÉRIAUX À COUCHE ISOLANTE POUR LA MICROÉLECTRONIQUE

Publication

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Application

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Abstract (en)

[origin: WO2007141048A1] The invention deals with the fields of microelectronics and material technology and relates to an insulation layer material for microelectronics which can be used, for example, in integrated circuits as a dielectric between copper conductor tracks. The invention addresses the problem of providing an insulation layer material for microelectronics which has a dielectricity constant of $k < 2$ whilst also having good mechanical properties. The problem is solved with an insulation layer material for microelectronics which consists of a plurality of fluorinated carbon nanotubes which are connected to a network, at least at certain points, by means of physical and/or chemical connections, using a bonding agent.

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